

- 56 -

ABSTRACT OF THE DISCLOSURE

5 A method for inspecting a photomask, comprising
generating a laser beam, changing a phase of the laser
beam to smooth the brightness distribution of the laser
beam, applying the smoothed laser beam to the photomask,
acquiring an image of the photomask using a sensor
while the laser beam and the photomask are relatively
moved, examining the image of the photomask for
a defect of the mask-pattern of the photomask.

09870702 050101